



DIE-TO-WAFER HIGH SPEED EQUIPMENT FOR DIRECT HYBRID BONDING



Pascal Metzger
SET, CEO

Leti Workshop @ Semicon West | July 10, 2018



TECHNOLOGY
RESEARCH
INSTITUTE



Institut de recherche
Technologique Nanoelec



Leti @ Semicon West 2018

From 7/10/2018 to 7/12/2018

📍 San Francisco, California

SET CORPORATION

SMART EQUIPMENT TECHNOLOGY

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WELCOME

Pascal METZGER

San Francisco, July 10th

SET Corporation AT A GLANCE

- Since **1975: Equipment for semiconductor**
celebrating 40 years in 2015!



- Since **1981: SET designs, assembles and sells high precision “flip-chip” bonders**

- **1st flip-chip bonder @ CEA-Leti in 1981**
- **Focusing since the beginning on thermocompression and high precision for pixelized sensors**
- **38 years of experience**
- **World leader in submicron bonding**

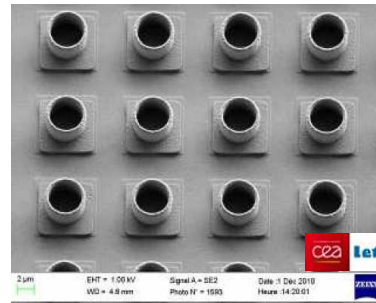
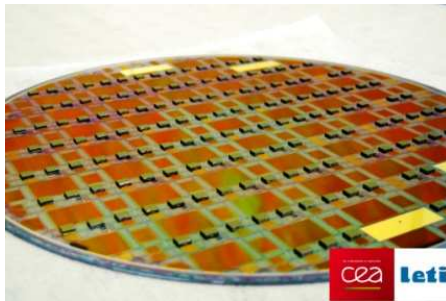
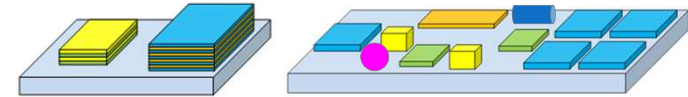


Adressed Markets, Applications and Processes

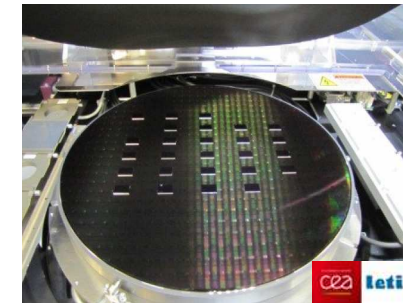
R&D: Research Institutes and Universities

Bonding

- RT compression, Thermocompression, Thermosonic, Thermal Curing, UV Curing, Reflow, Cu-Cu Direct Bonding...
- Heterogeneous integration, 3D



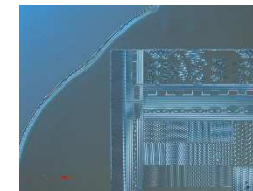
10⁶ μtubes - 10 μm pitch - RT process



Direct Cu-Cu bonding – RT process

Nanolithography

- UV-NIL (room temperature, UV lithography)
- HEL (Hot Embossing Lithography)



Courtesy: VTT (Finland)

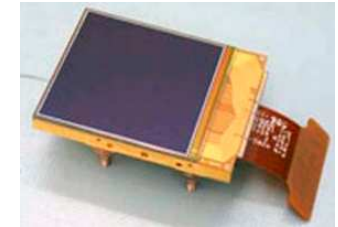
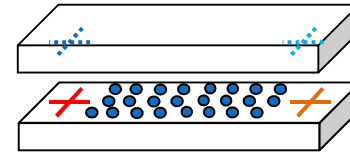


Adressed Markets, Applications and Processes

PRODUCTION: Industries

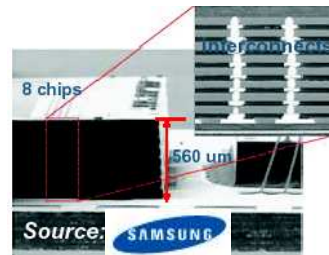
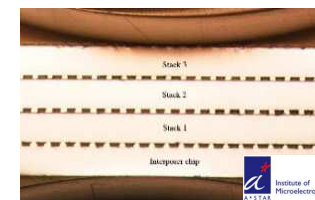
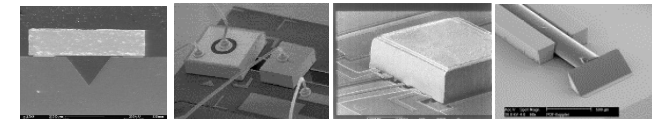
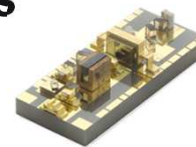
Pixelized Sensors (medical, aerospace, military and scientific)

- Up to 4k x 4k pixels
- Down to 10 μm pitch, even better



Production for commercial applications

- Hard Disks / HAMR / Optoelectronic
- Laser bars
- 3D-IC / Die to Die, Die to Wafer with TSV
- Mini/Micro screens
- MEMS / MOEMS
- Memories



PORTFOLIO

NPS300



$\pm 0,5 \mu\text{m}$ **FC 300**
Flip-Chip Bonder



$\pm 1 \mu\text{m}$ **FC 150**
Flip-Chip Bonder






LDP 150
Large Device Press

PERSPECTIVES



Trend

-  Size of devices,  Power consumption,  Speed communication
- Heterogeneous integration (3D) → D2W
- Finer pitch → High bonding precision
- Even for consumer market → High throughput



Consequences for chip designer, process designer and equipment supplier



Project

- Take into account all requirements (front and back end, chips, process, equipment)
- Process compatible with high throughput and high precision
- Equipment reaching all these requirements
- → RT Cu-Cu direct bonding
- → Cleanliness

Such equipment
does not exist today!

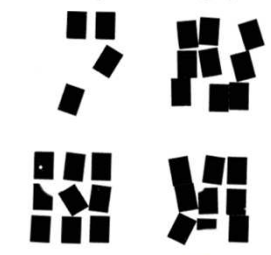
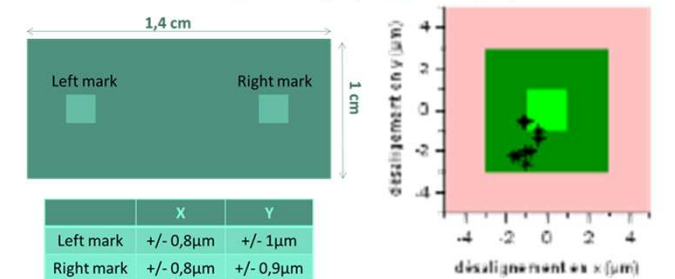
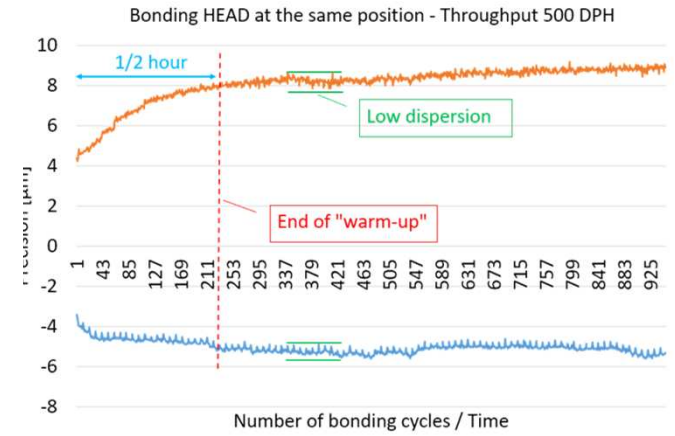


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PROJECT



Technical Characteristics	Target
Throughput	1000 dph
Precision	$\pm 1 \mu\text{m}$
Cleanliness	Compatible for Direct Bonding



PROJECT

Future development

- Collect measurements on precision, cleanliness, throughput for full qualification of beta tool
- Qualify the process on active device, full morphological and electrical characterization on Q4/2018
- Demonstrate, at Leti's site, on customers' components in Q4/2018
- Commercial launching in 2019
- SET aims to be a major player in 3D integration

Part of this work was funded thanks to the French national program "Programme d'Investissements d'Avenir, IRT Nanoelec" ANR-10-AIRT-05.





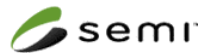
Thank you for your attention

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